

# Christopher K Ober

## List of Publications by Citations

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512 papers	25,996 citations	76 h-index	147 g-index
593 ext. papers	27,632 ext. citations	6.7 avg, IF	6.84 L-index

#	Paper	IF	Citations
512	Emerging applications of stimuli-responsive polymer materials. <i>Nature Materials</i> , <b>2010</b> , 9, 101-13	27	4474
511	Nanocomposite Materials for Optical Applications. <i>Chemistry of Materials</i> , <b>1997</b> , 9, 1302-1317	9.6	888
510	Advances in polymers for anti-biofouling surfaces. <i>Journal of Materials Chemistry</i> , <b>2008</b> , 18, 3405		680
509	An efficient two-photon-generated photoacid applied to positive-tone 3D microfabrication. <i>Science</i> , <b>2002</b> , 296, 1106-9	33.3	646
508	Competing Interactions and Levels of Ordering in Self-Organizing Polymeric Materials. <i>Science</i> , <b>1997</b> , 277, 1225-1232	33.3	643
507	Self-assembled monolayers and polymer brushes in biotechnology: current applications and future perspectives. <i>Biomacromolecules</i> , <b>2005</b> , 6, 2427-48	6.9	621
506	Attogram detection using nanoelectromechanical oscillators. <i>Journal of Applied Physics</i> , <b>2004</b> , 95, 3694-3703	37.93	475
505	Self-Assembled Smectic Phases in Rod-Coil Block Copolymers. <i>Science</i> , <b>1996</b> , 273, 343-6	33.3	385
504	Anti-biofouling properties of comblike block copolymers with amphiphilic side chains. <i>Langmuir</i> , <b>2006</b> , 22, 5075-86	4	312
503	Liquid Crystalline, Semifluorinated Side Group Block Copolymers with Stable Low Energy Surfaces: Synthesis, Liquid Crystalline Structure, and Critical Surface Tension. <i>Macromolecules</i> , <b>1997</b> , 30, 1906-1914	5.5	291
502	Particle size control in dispersion polymerization of polystyrene. <i>Canadian Journal of Chemistry</i> , <b>1985</b> , 63, 209-216	0.9	289
501	50th Anniversary Perspective: Polymer Brushes: Novel Surfaces for Future Materials. <i>Macromolecules</i> , <b>2017</b> , 50, 4089-4113	5.5	265
500	Comparison of the fouling release properties of hydrophobic fluorinated and hydrophilic PEGylated block copolymer surfaces: attachment strength of the diatom <i>Navicula</i> and the green alga <i>Ulva</i> . <i>Biomacromolecules</i> , <b>2006</b> , 7, 1449-62	6.9	238
499	Polyelectrolyte-Surfactant Complexes in the Solid State: Facile building blocks for self-organizing materials. <i>Advanced Materials</i> , <b>1997</b> , 9, 17-31	24	233
498	Surface Segregation Studies of Fluorine-Containing Diblock Copolymers. <i>Macromolecules</i> , <b>1996</b> , 29, 1229-1234	5.5	217
497	Molecular Design, Synthesis, and Characterization of Liquid Crystalline Coil Diblock Copolymers with Azobenzene Side Groups. <i>Macromolecules</i> , <b>1997</b> , 30, 2556-2567	5.5	209
496	Block copolymer patterns and templates. <i>Materials Today</i> , <b>2006</b> , 9, 30-39	21.8	196

495	Zigzag Morphology of a Poly(styrene-b-hexyl isocyanate) Rod-Coil Block Copolymer. <i>Macromolecules</i> , <b>1995</b> , 28, 1688-1697	5.5	192
494	Recent progress in high resolution lithography. <i>Polymers for Advanced Technologies</i> , <b>2006</b> , 17, 94-103	3.2	191
493	Study of the interlayer expansion mechanism and thermal/mechanical properties of surface-initiated epoxy nanocomposites. <i>Polymer</i> , <b>2002</b> , 43, 4895-4904	3.9	177
492	Monodispersed, micron-sized polystyrene particles by dispersion polymerization. <i>Journal of Polymer Science, Polymer Letters Edition</i> , <b>1985</b> , 23, 103-108		166
491	Reworkable Epoxies: Thermosets with Thermally Cleavable Groups for Controlled Network Breakdown. <i>Chemistry of Materials</i> , <b>1998</b> , 10, 1475-1482	9.6	162
490	Formation of large monodisperse copolymer particles by dispersion polymerization. <i>Macromolecules</i> , <b>1987</b> , 20, 268-273	5.5	160
489	Thermotropic Liquid Crystalline Polyesters with Rigid or Flexible Spacer Groups. <i>British Polymer Journal</i> , <b>1980</b> , 12, 132-146		158
488	An overview of supercritical CO2 applications in microelectronics processing. <i>Microelectronic Engineering</i> , <b>2003</b> , 65, 145-152	2.5	157
487	Orthogonal Patterning of PEDOT:PSS for Organic Electronics using Hydrofluoroether Solvents. <i>Advanced Materials</i> , <b>2009</b> , 21, 2314-2317	24	146
486	Deformation of a Polydomain, Liquid Crystalline Epoxy-Based Thermoset. <i>Macromolecules</i> , <b>1998</b> , 31, 4074-4088	5.5	146
485	Reversible Morphology Control in Block Copolymer Films via Solvent Vapor Processing: An In Situ GISAXS study. <i>Macromolecules</i> , <b>2010</b> , 43, 4253-4260	5.5	144
484	Dissociation behavior of weak polyelectrolyte brushes on a planar surface. <i>Langmuir</i> , <b>2009</b> , 25, 4774-9	4	140
483	Research in Macromolecular Science: Challenges and Opportunities for the Next Decade. <i>Macromolecules</i> , <b>2009</b> , 42, 465-471	5.5	139
482	Liquid crystalline and rigid-rod networks. <i>Progress in Polymer Science</i> , <b>1993</b> , 18, 899-945	29.6	137
481	Control of biofouling on reverse osmosis polyamide membranes modified with biocidal nanoparticles and antifouling polymer brushes. <i>Journal of Materials Chemistry B</i> , <b>2014</b> , 2, 1724-1732	7.3	135
480	ABC triblock surface active block copolymer with grafted ethoxylated fluoroalkyl amphiphilic side chains for marine antifouling/fouling-release applications. <i>Langmuir</i> , <b>2009</b> , 25, 12266-74	4	135
479	Patterned biofunctional poly(acrylic acid) brushes on silicon surfaces. <i>Biomacromolecules</i> , <b>2007</b> , 8, 3082-92	3.9	131
478	Control of self-assembly of lithographically patternable block copolymer films. <i>ACS Nano</i> , <b>2008</b> , 2, 1396-407	4.7	130

477	Hydrofluoroethers as Orthogonal Solvents for the Chemical Processing of Organic Electronic Materials. <i>Advanced Materials</i> , <b>2008</b> , 20, 3481-3484	24	128
476	Reinforcement of polymer interfaces with random copolymers. <i>Physical Review Letters</i> , <b>1994</b> , 73, 2472-2475	3.4	128
475	Oligo(ethylene glycol) containing polymer brushes as bioselective surfaces. <i>Langmuir</i> , <b>2005</b> , 21, 2495-504	3.4	125
474	Extreme ultraviolet resist materials for sub-7 nm patterning. <i>Chemical Society Reviews</i> , <b>2017</b> , 46, 4855-4865	3.6	124
473	Characterization of thermally reworkable thermosets: materials for environmentally friendly processing and reuse. <i>Polymer</i> , <b>2002</b> , 43, 131-139	3.9	124
472	Coatings based on side-chain ether-linked poly(ethylene glycol) and fluorocarbon polymers for the control of marine biofouling. <i>Biofouling</i> , <b>2003</b> , 19 Suppl, 91-8	3.3	121
471	Alignment of Self-Assembled Hierarchical Microstructure in Liquid Crystalline Diblock Copolymers Using High Magnetic Fields. <i>Macromolecules</i> , <b>2004</b> , 37, 9903-9908	5.5	117
470	Settlement of Ulva zoospores on patterned fluorinated and PEGylated monolayer surfaces. <i>Langmuir</i> , <b>2008</b> , 24, 503-10	4	116
469	Surfaces of fluorinated pyridinium block copolymers with enhanced antibacterial activity. <i>Langmuir</i> , <b>2006</b> , 22, 11255-66	4	114
468	Patternable Block Copolymers		113
467	The Orientation of Semifluorinated Alkanes Attached to Polymers at the Surface of Polymer Films. <i>Macromolecules</i> , <b>2000</b> , 33, 1882-1887	5.5	109
466	The effect of temperature and initiator levels on the dispersion polymerization of polystyrene. <i>Journal of Polymer Science Part A</i> , <b>1987</b> , 25, 1395-1407	2.5	107
465	Semifluorinated Aromatic Side-Group Polystyrene-Based Block Copolymers: Bulk Structure and Surface Orientation Studies. <i>Macromolecules</i> , <b>2002</b> , 35, 8078-8087	5.5	105
464	Release of nerve growth factor from HEMA hydrogel-coated substrates and its effect on the differentiation of neural cells. <i>Biomacromolecules</i> , <b>2009</b> , 10, 174-83	6.9	103
463	Surface Stability in Liquid-Crystalline Block Copolymers with Semifluorinated Monodendron Side Groups. <i>Macromolecules</i> , <b>2000</b> , 33, 6106-6119	5.5	103
462	A general approach to controlling the surface composition of poly(ethylene oxide)-based block copolymers for antifouling coatings. <i>Langmuir</i> , <b>2011</b> , 27, 13762-72	4	102
461	Rigid rod and liquid crystalline thermosets. <i>Progress in Polymer Science</i> , <b>1997</b> , 22, 975-1000	29.6	100
460	Self-Organizing Materials with Low Surface Energy: The Synthesis and Solid-State Properties of Semifluorinated Side-Chain Ionenenes. <i>Macromolecules</i> , <b>1997</b> , 30, 7560-7567	5.5	99

459	Design and application of high-sensitivity two-photon initiators for three-dimensional microfabrication. <i>Journal of Photochemistry and Photobiology A: Chemistry</i> , <b>2003</b> , 158, 163-170	4.7	98
458	Liquid Crystal Polymers. V. Thermotropic Polyesters with Either Dyad or Triad Aromatic Ester Mesogenic Units and Flexible Polymethylene Spacers in the Main Chain. <i>Polymer Journal</i> , <b>1982</b> , 14, 9-17	2.7	98
457	Direct three-dimensional microfabrication of hydrogels via two-photon lithography in aqueous solution. <i>Chemistry of Materials</i> , <b>2009</b> , 21, 2003-2006	9.6	96
456	Synthesis and Characterization of Thermally Degradable Polymer Networks. <i>Chemistry of Materials</i> , <b>1998</b> , 10, 3833-3838	9.6	96
455	Liquid crystalline epoxy thermosets based on dihydroxymethylstilbene: Synthesis and characterization. <i>Journal of Polymer Science Part A</i> , <b>1992</b> , 30, 1831-1843	2.5	96
454	Fluorinated amphiphilic polymers and their blends for fouling-release applications: the benefits of a triblock copolymer surface. <i>ACS Applied Materials &amp; Interfaces</i> , <b>2011</b> , 3, 3366-74	9.5	95
453	Spatially Controlled Fabrication of Nanoporous Block Copolymers. <i>Chemistry of Materials</i> , <b>2004</b> , 16, 3800-3808	9.3	95
452	Additive-Driven Phase-Selective Chemistry in Block Copolymer Thin Films: The Convergence of Top-Down and Bottom-Up Approaches. <i>Advanced Materials</i> , <b>2004</b> , 16, 953-957	24	93
451	Controlled degradation of epoxy networks: analysis of crosslink density and glass transition temperature changes in thermally reworkable thermosets. <i>Polymer</i> , <b>2004</b> , 45, 1939-1950	3.9	93
450	Orthogonal processing: A new strategy for organic electronics. <i>Chemical Science</i> , <b>2011</b> , 2, 1178	9.4	92
449	Molecular Glass Resists for High-Resolution Patterning. <i>Chemistry of Materials</i> , <b>2006</b> , 18, 3404-3411	9.6	92
448	Amphiphilic surface active triblock copolymers with mixed hydrophobic and hydrophilic side chains for tuned marine fouling-release properties. <i>Langmuir</i> , <b>2010</b> , 26, 9772-81	4	90
447	Triblock Copolymers with Grafted Fluorine-Free, Amphiphilic, Non-Ionic Side Chains for Antifouling and Fouling-Release Applications. <i>Macromolecules</i> , <b>2011</b> , 44, 4783-4792	5.5	89
446	Block copolymers containing liquid crystalline segments. <i>Acta Polymerica</i> , <b>1997</b> , 48, 405-422		89
445	Deformation of a Polydomain, Smectic Liquid Crystalline Elastomer. <i>Macromolecules</i> , <b>1998</b> , 31, 8531-8539	9.5	89
444	Low-Surface-Energy Fluoromethacrylate Block Copolymers with Patternable Elements. <i>Chemistry of Materials</i> , <b>2000</b> , 12, 33-40	9.6	88
443	Two-Photon Three-Dimensional Microfabrication of Poly(Dimethylsiloxane) Elastomers. <i>Chemistry of Materials</i> , <b>2004</b> , 16, 5556-5558	9.6	87
442	The mechanical and magnetic alignment of liquid crystalline epoxy thermosets. <i>Journal of Polymer Science Part A</i> , <b>1992</b> , 30, 1845-1853	2.5	85

441	Stress relaxation of a main-chain, smectic, polydomain liquid crystalline elastomer. <i>Polymer</i> , <b>1998</b> , 39, 3713-3718	3.9	83
440	Supercritical CO <sub>2</sub> Processing for Submicron Imaging of Fluoropolymers. <i>Chemistry of Materials</i> , <b>2000</b> , 12, 41-48	9.6	81
439	Fluorine-free mixed amphiphilic polymers based on PDMS and PEG side chains for fouling release applications. <i>Biofouling</i> , <b>2011</b> , 27, 589-602	3.3	80
438	Control of surface properties using fluorinated polymer brushes produced by surface-initiated controlled radical polymerization. <i>Langmuir</i> , <b>2004</b> , 20, 10498-506	4	78
437	Protein adsorption resistance of anti-biofouling block copolymers containing amphiphilic side chains. <i>Soft Matter</i> , <b>2010</b> , 6, 3237	3.6	76
436	Temperature Dependence of Molecular Orientation on the Surfaces of Semifluorinated Polymer Thin Films. <i>Langmuir</i> , <b>2000</b> , 16, 1993-1997	4	76
435	Role of solvent dielectric properties on charge transfer from PbS nanocrystals to molecules. <i>Nano Letters</i> , <b>2010</b> , 10, 318-23	11.5	73
434	High-performance electron-transporting polymers derived from a heteroaryl bis(trifluoroborate). <i>Journal of the American Chemical Society</i> , <b>2011</b> , 133, 9949-51	16.4	72
433	Liquid Crystalline Rod-Coil Block Copolymers by Stable Free Radical Polymerization: Synthesis, Morphology, and Rheology. <i>Macromolecules</i> , <b>2003</b> , 36, 3357-3364	5.5	72
432	Engineering low surface energy polymers through molecular design: synthetic routes to fluorinated polystyrene-based block copolymers. <i>Journal of Materials Chemistry</i> , <b>2002</b> , 12, 1684-1692		71
431	Rigid-rod thermosets based on 1,3,5-triazine-linked aromatic ester segments. <i>Macromolecules</i> , <b>1992</b> , 25, 2947-2954	5.5	71
430	Widely Tunable Morphologies in Block Copolymer Thin Films Through Solvent Vapor Annealing Using Mixtures of Selective Solvents. <i>Advanced Functional Materials</i> , <b>2015</b> , 25, 3057-3065	15.6	70
429	Amplification by optical composites. <i>Optics Letters</i> , <b>1997</b> , 22, 1247-9	3	69
428	Synthesis and curing of novel LC twin epoxy monomers for liquid crystal thermosets. <i>Journal of Polymer Science Part A</i> , <b>1996</b> , 34, 1291-1303	2.5	69
427	Synthesis and characterization of pyrene-labeled hydroxypropyl cellulose and its fluorescence in solution. <i>Macromolecules</i> , <b>1987</b> , 20, 38-44	5.5	69
426	Molecular glass photoresists for advanced lithography. <i>Journal of Materials Chemistry</i> , <b>2006</b> , 16, 1693		68
425	Detection of transmitter release from single living cells using conducting polymer microelectrodes. <i>Advanced Materials</i> , <b>2011</b> , 23, H184-8	24	67
424	Sub-50 nm feature sizes using positive tone molecular glass resists for EUV lithography. <i>Journal of Materials Chemistry</i> , <b>2006</b> , 16, 1470		66

423	Understanding and controlling the morphology of styrene- <i>isoprene</i> side-group liquid crystalline diblock copolymers. <i>Polymer</i> , <b>2000</b> , 41, 8897-8907	3.9	65
422	Direct patterning of intrinsically electron beam sensitive polymer brushes. <i>ACS Nano</i> , <b>2010</b> , 4, 771-80	16.7	64
421	Methods for the topographical patterning and patterned surface modification of hydrogels based on hydroxyethyl methacrylate. <i>Biomacromolecules</i> , <b>2003</b> , 4, 1126-31	6.9	64
420	Orientation of Liquid Crystalline Epoxides under ac Electric Fields. <i>Macromolecules</i> , <b>1997</b> , 30, 4278-4287	5.5	63
419	Zinc induced polyelectrolyte coacervate bioadhesive and its transition to a self-healing hydrogel. <i>RSC Advances</i> , <b>2015</b> , 5, 66871-66878	3.7	62
418	Electrical control of protein conformation. <i>Advanced Materials</i> , <b>2012</b> , 24, 2501-5	24	62
417	Acid-sensitive semiperfluoroalkyl resorcinarene: an imaging material for organic electronics. <i>Journal of the American Chemical Society</i> , <b>2008</b> , 130, 11564-5	16.4	62
416	Chemically Amplified Positive Resists for Two-Photon Three-Dimensional Microfabrication. <i>Advanced Materials</i> , <b>2003</b> , 15, 517-521	24	62
415	Fluorinated mesogen-jacketed liquid-crystalline polymers as surface-modifying agents: Design, synthesis and characterization. <i>Macromolecular Chemistry and Physics</i> , <b>2002</b> , 203, 1573-1583	2.6	60
414	Orientation-On-Demand Thin Films: Curing of Liquid Crystalline Networks in ac Electric Fields. <i>Science</i> , <b>1996</b> , 272, 252-255	33.3	60
413	Polymer-Based Marine Antifouling and Fouling Release Surfaces: Strategies for Synthesis and Modification. <i>Annual Review of Chemical and Biomolecular Engineering</i> , <b>2019</b> , 10, 241-264	8.9	59
412	Amphiphilic triblock copolymers with PEGylated hydrocarbon structures as environmentally friendly marine antifouling and fouling-release coatings. <i>Biofouling</i> , <b>2014</b> , 30, 589-604	3.3	57
411	Orientational Switching of Mesogens and Microdomains in Hydrogen-Bonded Side-Chain Liquid-Crystalline Block Copolymers Using AC Electric Fields. <i>Advanced Functional Materials</i> , <b>2004</b> , 14, 364-370	15.6	57
410	Polymer brushes for electrochemical biosensors. <i>Soft Matter</i> , <b>2011</b> , 7, 297-302	3.6	55
409	Selective area control of self-assembled pattern architecture using a lithographically patternable block copolymer. <i>ACS Nano</i> , <b>2009</b> , 3, 1761-6	16.7	54
408	Transverse Cylindrical Microdomain Orientation in an LC Diblock Copolymer under Oscillatory Shear. <i>Macromolecules</i> , <b>1999</b> , 32, 7703-7706	5.5	54
407	Surface organization, light-driven surface changes, and stability of semifluorinated azobenzene polymers. <i>Langmuir</i> , <b>2007</b> , 23, 5110-9	4	53
406	Surface engineering of styrene/PEGylated-fluoroalkyl styrene block copolymer thin films. <i>Journal of Polymer Science Part A</i> , <b>2009</b> , 47, 267-284	2.5	52



405	Studying the Mechanism of Hybrid Nanoparticle Photoresists: Effect of Particle Size on Photopatterning. <i>Chemistry of Materials</i> , <b>2015</b> , 27, 5027-5031	9.6	51
404	Linear viscoelasticity of side chain liquid crystal polymer. <i>Liquid Crystals</i> , <b>1993</b> , 13, 233-245	2.3	51
403	A glucose sensor via stable immobilization of the GOx enzyme on an organic transistor using a polymer brush. <i>Journal of Polymer Science Part A</i> , <b>2015</b> , 53, 372-377	2.5	50
402	High refractive index and high transparency HfO <sub>2</sub> nanocomposites for next generation lithography. <i>Journal of Materials Chemistry</i> , <b>2010</b> , 20, 5186		50
401	Smectic rheology. <i>Rheologica Acta</i> , <b>1997</b> , 36, 498-504	2.3	50
400	Molecular Orientation of Single and Two-Armed Monodendron Semifluorinated Chains on Soft and Hard Surfaces Studied Using NEXAFS. <i>Macromolecules</i> , <b>2000</b> , 33, 6068-6077	5.5	50
399	Fluorinated polymers: liquid crystalline properties and applications in lithography. <i>Chemical Record</i> , <b>2004</b> , 4, 315-30	6.6	49
398	Effect of Changing Molecular End Groups on Surface Properties: Synthesis and Characterization of Poly(styrene- <i>b</i> -semifluorinated isoprene) Block Copolymers with F <sub>2</sub> H End Groups. <i>Macromolecules</i> , <b>2000</b> , 33, 8012-8019	5.5	49
397	Block copolymers with low surface energy segments: siloxane- and perfluoroalkane-modified blocks. <i>Polymer</i> , <b>1995</b> , 36, 1321-1325	3.9	49
396	An Efficient Route to Mesoporous Silica Films with Perpendicular Nanochannels. <i>Advanced Materials</i> , <b>2008</b> , 20, 246-251	24	48
395	Microphase-Stabilized Ferroelectric Liquid Crystals (MSFLC): Bistable Switching of Ferroelectric Liquid Crystal Coil Diblock Copolymers. <i>Chemistry of Materials</i> , <b>1998</b> , 10, 1538-1545	9.6	48
394	Mesogen-jacketed liquid crystalline polymers via stable free radical polymerization. <i>Macromolecular Chemistry and Physics</i> , <b>1999</b> , 200, 2338-2344	2.6	48
393	Perpendicular Orientation Control without Interfacial Treatment of RAFT-Synthesized High-Block Copolymer Thin Films with Sub-10 nm Features Prepared via Thermal Annealing. <i>ACS Applied Materials &amp; Interfaces</i> , <b>2017</b> , 9, 31266-31278	9.5	47
392	Selectively Thermally Cleavable Fluorinated Side Chain Block Copolymers: Surface Chemistry and Surface Properties. <i>Macromolecules</i> , <b>2000</b> , 33, 1310-1320	5.5	47
391	Responsive and patterned polymer brushes. <i>Journal of Polymer Science, Part B: Polymer Physics</i> , <b>2013</b> , 51, 1457-1472	2.6	46
390	A novel noria (water-wheel-like cyclic oligomer) derivative as a chemically amplified electron-beam resist material. <i>Journal of Materials Chemistry</i> , <b>2008</b> , 18, 3588		46
389	Control and Suppression of Surface Relief Gratings in Liquid-Crystalline Perfluoroalkyl Azobenzene Polymers. <i>Advanced Functional Materials</i> , <b>2006</b> , 16, 1577-1581	15.6	46
388	Antimicrobial behavior of semifluorinated-quaternized triblock copolymers against airborne and marine microorganisms. <i>ACS Applied Materials &amp; Interfaces</i> , <b>2010</b> , 2, 703-11	9.5	45



387	Role of Backbone Chemistry and Monomer Sequence in Amphiphilic Oligopeptide- and Oligopeptoid-Functionalized PDMS- and PEO-Based Block Copolymers for Marine Antifouling and Fouling Release Coatings. <i>Macromolecules</i> , <b>2017</b> , 50, 2656-2667	5.5	44
386	Patterning of polymer brushes. A direct approach to complex, sub-surface structures. <i>Nano Letters</i> , <b>2010</b> , 10, 3873-9	11.5	44
385	Functionalized surface arrays for spatial targeting of immune cell signaling. <i>Journal of the American Chemical Society</i> , <b>2006</b> , 128, 5594-5	16.4	44
384	Rod-coil block copolymers: An iterative synthetic approach via living free-radical procedures. <i>Journal of Polymer Science Part A</i> , <b>2003</b> , 41, 3640-3656	2.5	44
383	Viscoelastic properties of a model main-chain liquid crystalline polyether. <i>Journal of Rheology</i> , <b>1994</b> , 38, 1623-1638	4.1	44
382	Ambiguous anti-fouling surfaces: Facile synthesis by light-mediated radical polymerization. <i>Journal of Polymer Science Part A</i> , <b>2016</b> , 54, 253-262	2.5	44
381	NEXAFS Depth Profiling of Surface Segregation in Block Copolymer Thin Films. <i>Macromolecules</i> , <b>2010</b> , 43, 4733-4743	5.5	43
380	Surface Induced Tilt Propagation in Thin Films of Semifluorinated Liquid Crystalline Side Chain Block Copolymers. <i>Macromolecules</i> , <b>2007</b> , 40, 81-89	5.5	42
379	High-Resolution Patterning of Molecular Glasses Using Supercritical Carbon Dioxide. <i>Advanced Materials</i> , <b>2006</b> , 18, 442-446	24	41
378	Cellular responses to patterned poly(acrylic acid) brushes. <i>Langmuir</i> , <b>2011</b> , 27, 7016-23	4	40
377	Analysis of smectic structure formation in liquid crystalline thermosets. <i>Polymer</i> , <b>1997</b> , 38, 5857-5867	3.9	40
376	Biomimetic polymer brushes containing tethered acetylcholine analogs for protein and hippocampal neuronal cell patterning. <i>Biomacromolecules</i> , <b>2013</b> , 14, 529-37	6.9	39
375	Fouling-resistant polymer brush coatings. <i>Polymer</i> , <b>2011</b> , 52, 5419-5425	3.9	39
374	Characterization of the Photoacid Diffusion Length and Reaction Kinetics in EUV Photoresists with IR Spectroscopy. <i>Macromolecules</i> , <b>2010</b> , 43, 4275-4286	5.5	39
373	Dry photolithographic patterning process for organic electronic devices using supercritical carbon dioxide as a solvent. <i>Journal of Materials Chemistry</i> , <b>2008</b> , 18, 3087		39
372	Three-Dimensional Microfabrication by Two-Photon Lithography. <i>MRS Bulletin</i> , <b>2005</b> , 30, 976-982	3.2	39
371	Liquid-crystalline polymers. 12. Polyesters with either alternating or random orientation of mesogenic units. <i>Macromolecules</i> , <b>1983</b> , 16, 1034-1036	5.5	38
370	Effects of surface-active block copolymers with oxyethylene and fluoroalkyl side chains on the antifouling performance of silicone-based films. <i>Biofouling</i> , <b>2016</b> , 32, 81-93	3.3	37

- 369 Reconstruction of surfaces from mixed hydrocarbon and PEG components in water: responsive surfaces aid fouling release. *Biomacromolecules*, **2012**, 13, 1864-74 6.9 37
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